

L Number	Hits	Search Text	DB	Time stamp
1	121	((no or (nitric with oxide)) and cvd and (nitrogen with dop\$3 with oxide) and (thermal adj oxidation))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 15:58
2	108	((no or (nitric with oxide)) and cvd and (nitrogen with dop\$3 with oxide) and (thermal adj oxidation)) and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 15:59
3	100	("no".u/c. or (nitric with oxide)) and cvd and (nitrogen with dop\$3 with oxide) and (thermal adj oxidation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:14
4	93	((("no".u/c. or (nitric with oxide)) and cvd and (nitrogen with dop\$3 with oxide) and (thermal adj oxidation)) and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:15
5	88	("no".u/c. or (nitric with oxide)) and cvd and ((thermal adj oxidation) same (thermal adj nitridation))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:15
6	85	((("no".u/c. or (nitric with oxide)) and cvd and ((thermal adj oxidation) same (thermal adj nitridation))) and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:32
7	2	("no".u/c. or (nitric with oxide)) and cvd and ((thermal adj oxidation) same (thermal adj nitridation) same (gate adj oxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:32
8	31	("no".u/c. or (nitric with oxide)) and cvd and ((thermal adj oxidation) same (gate adj oxide)) and (thermal adj nitridation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:32
9	30	((("no".u/c. or (nitric with oxide)) and cvd and ((thermal adj oxidation) same (gate adj oxide)) and (thermal adj nitridation)) and (@ad<20011012 or @rlad<20011012)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/08 18:32
-	355	(gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd	USPAT; EPO; JPO; DERWENT	2004/01/08 15:52
-	197	((gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	149	((gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr) and 438/\$3.ccls.	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	119	((gate with oxide) and (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr) and 438/\$3.ccls.) and (gate with electrode)	USPAT; EPO; JPO; DERWENT	2002/07/30 13:55
-	145	(gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd	USPAT; EPO; JPO; DERWENT	2002/07/31 15:55
-	76	((gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr)	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02
-	59	((gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd) and temperature and (atm or atmosphere or torr) and 438/\$3.ccls.	USPAT; EPO; JPO; DERWENT	2002/07/30 14:02

-	5	(gate with oxide) same (oxidiz\$3 with substrate) and ((nitrid\$5 with (no or (nitric with oxide)) same boron)) and cvd	USPAT; EPO; JPO; DERWENT	2002/07/30 15:11
-	17	"5650344"	USPAT; EPO; JPO; DERWENT	2002/07/30 15:11
-	14	"5403786"	USPAT; EPO; JPO; DERWENT	2002/07/31 14:16
-	26	(gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd and ono and (gate adj electrode)	USPAT; EPO; JPO; DERWENT	2002/07/31 15:57
-	22	(gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd and ono and ((gate adj electrode) with (silicon or polysilicon))	USPAT; EPO; JPO; DERWENT	2002/07/31 16:33
-	11	((gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd and ono and ((gate adj electrode) with (silicon or polysilicon))) and tungsten	USPAT; EPO; JPO; DERWENT	2002/07/31 15:58
-	3	(gate with oxide) same (oxidiz\$3 with substrate) and (nitrid\$5 with (no or (nitric with oxide))) and cvd and ono and ((gate adj electrode) with polycide) same tungsten	USPAT; EPO; JPO; DERWENT	2002/07/31 16:56
-	17	"5650344"	USPAT; EPO; JPO; DERWENT	2002/07/31 16:56
-	3554	(nitrid\$5 with gate with oxide) and cvd	USPAT; EPO; JPO; DERWENT	2003/01/13 12:32
-	0	((nitrid\$5 with gate with oxide) same (nitirc adj oxide)) and cvd	USPAT; EPO; JPO; DERWENT	2003/01/13 12:33
-	5	((nitrid\$5 with gate with oxide) same (nitric adj oxide)) and cvd	USPAT; EPO; JPO; DERWENT	2003/01/13 12:33
-	6	((nitrid\$5 with gate with oxide) same (nitric adj oxide)) and cvd	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 14:55
-	0	11040681.URPN.	USPAT	2003/01/13 14:46
-	2	5726087.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 16:28
-	355	dry adj oxide	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 16:49
-	518	(gate adj oxide) with angstrom with ("10" or "15" or "20")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 16:51
-	341	(gate adj oxide) with angstrom with ("10" or "15")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:23
-	234	((gate adj oxide) with angstrom with ("10" or "15")) and nitrid\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:06
-	46	((gate adj oxide) with angstrom with ("10" or "15")) same nitrid\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:06

-	8	(gate adj oxide) with angstrom with ("10" or "15") with (ultra near2 thin)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/01/13 17:24
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